

## Notation

$T$	temperature, K
$p$	pressure, Pa
$v$	specific volume, $\text{m}^3/\text{kg}$
$V_\mu$	molal volume, $\text{m}^3/\text{kmol}$
$M$	molecular mass
$c_p$	specific isobaric heat capacity, $\text{kJ}/(\text{kg}\cdot\text{K})$
$c_v$	specific isohoric heat capacity, $\text{kJ}/(\text{kg}\cdot\text{K})$
$\lambda$	thermal conductivity, $\text{W}/(\text{m}\cdot\text{K})$
$\eta$	viscosity, dynamic, $\text{Pa}\cdot\text{c}$
$\nu$	viscosity kinematic, $\text{m}^2/\text{c}$
$\rho$	density, $\text{kg}/\text{m}^3$
$\Delta H_{\text{vap}}$	enthalpy change during vaporization (heat of vaporization), $\text{kJ}/\text{kmol}$
$\sigma$	surface tension, $\text{N}/\text{m}$
$a$	thermal diffusivity, $\text{m}^2/\text{c}$
$n_D^{20}$	refraction index at $T = 293.15 \text{ K}$
$z$	compressibility factor
$R$	gas constant, $\text{kJ}/(\text{kg}\cdot\text{K})$
$R_\mu$	universal gas constant
$\tau = T/T_{\text{cr}}$	reduced temperature
$\pi = p/p_{\text{cr}}$	reduced pressure
$\varphi = v/v_{\text{cr}}$	reducer volume
$x$	property to be found
$\omega_i$	contribution of a chemical structure element to the property to be found
$\varepsilon$	ratio of a number of methyl radicals ( $\text{CH}_3$ ) to a number of phenyl radicals ( $\text{C}_6\text{H}_5$ ) in an organosilicon molecule
$R_D$	mole refraction

## Subscripts

liq	liquid
v	vapor
gl	glass transition
cr	critical state
s	saturation
id	ideal-gas state
melt	melting
boil	boiling
vap	vaporization
td	thermal decomposition